

Title (en)

GRINDING SYSTEM FOR GRINDING A MATERIAL TO BE GROUND, AND METHOD FOR GRINDING A MATERIAL TO BE GROUND

Title (de)

MAHLANLAGE ZUM ZERKLEINERN VON MAHLGUT SOWIE VERFAHREN ZUM ZERKLEINERN VON MAHLGUT

Title (fr)

INSTALLATION DE BROyage POUR PULVÉRISER UNE MATIÈRE À BROyer ET PROCÉDÉ DE PULVÉRISATION DE MATIÈRE À BROyer

Publication

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Application

**EP 15750755 A 20150818**

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Abstract (en)

[origin: WO2016062428A1] The invention relates to a grinding system (10) for grinding a material to be ground, comprising at least one grinding device (12, 16) and a sifting device (14) connected to the at least one grinding device (12, 16) for sifting the ground material with a static sifter and a dynamic sifter, wherein the static sifter is arranged in such a way that it at least partially surrounds the dynamic sifter, wherein the sifting device (14) has at least one coarse material outlet (24) for releasing a coarse material having a coarse grain fraction, at least one grit outlet (26) for releasing a grit having a medium grain fraction, and at least one finished material outlet (28) for releasing a finished material having a fine grain fraction, wherein the grinding system has a control/regulation device for controlling/regulating at least one part of the flow of material to be ground to the at least one grinding device (12, 16). The invention also relates to a method for grinding a material to be ground, comprising at least the following steps: grinding the material to be ground in at least one grinding device (12, 16); sifting the ground material in a sifting device (14) into coarse material, grit and fine material, wherein the sifting device (14) has a static sifter and a dynamic sifter, wherein the static sifter is arranged in such a way that it at least partially surrounds the dynamic sifter, and wherein the flow of material to be ground to the at least one grinding device (12, 16) is controlled/regulated by means of a control/regulation device.

IPC 8 full level

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